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研究課題名(和文) Fabrication of Weyl semimetals based spintronic heterostructures for future energy-efficient IT devices  
研究課題名(英文) Fabrication of Weyl semimetals based spintronic heterostructures for future energy-efficient IT devices  
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研究成果の概要(和文)：The Weyl semimetal films of WTe<sub>2</sub> and MoTe<sub>2</sub> were fabricated by sputtering for the first time. A sizeable spin Hall effect was achieved in the Weyl semimetals. Furthermore, Co<sub>2</sub>MnGa Weyl semimetal thin films were fabricated and the degree of order dependence of anomalous Hall effect was discovered.

#### 研究成果の学術的意義や社会的意義

The experimental demonstration of the spin-orbit effects in Weyl semimetals in this research can contribute the progress of the developments of topological spintronic devices, which could provide an essential way of achieving energy-efficient IT devices for realizing the super-smart society.

研究成果の概要(英文)：In this research, the Weyl semimetal films of WTe<sub>2</sub> and MoTe<sub>2</sub> were fabricated by sputtering for the first time. By combining with CoFeB/AlO<sub>x</sub>, spin Hall magnetoresistance was investigated. A sizeable spin Hall effect was achieved in the sputtered WTe<sub>2</sub> Weyl semimetal based spintronic structures. Furthermore, Co<sub>2</sub>MnGa Weyl semimetal thin films were fabricated by sputtering method and the spin-orbit effects in the films were studied. A large anomalous Hall angle of ~14% was achieved. It is also observed that the anomalous Hall effect strongly depends on the degree of order of the Co<sub>2</sub>MnGa Weyl semimetals. The samples containing L21-ordered phase show enhanced anomalous Hall effect compared to B2-ordered samples. The reason could be the different electronic structures between the two ordered phases. The experimental demonstration of the spin orbit effects in sputtered Weyl semimetals could contribute the progress of the development of topological spintronic devices.

研究分野：磁性・スピントロニクス材料

キーワード：Weyl semimetals Spintronic structures Spin-orbit effects

### 1. 研究開始当初の背景

Energy-efficient and environment-friendly information technology (IT) devices are indispensable for establishing a super-smart and sustainable society. However, the properties of conventional materials are limited to further improve the performance of IT devices and cannot satisfy the energy-efficient memory and computing. Developing high-performance spintronic materials/heterostructures is an essential way of achieving future energy-efficient IT devices for realizing super-smart systems with various functionalities.

### 2. 研究の目的

The purpose of this research is to design and fabricate Weyl semimetals (WSs) based spintronic heterostructures for achieving high-performance and energy-efficient spintronic devices. The Weyl semimetal is a topologically nontrivial phase of matter that was discovered recently. Because of a large Berry curvature in their band structures, the WSs have been theoretically predicted to have large spin-orbit effects. Experimental demonstration of the WSs-based spintronic devices in this research will be of particular importance for realizing super-smart systems, such as internet of things (IoT) and artificial intelligence (AI) networks.

### 3. 研究の方法

According to the condition of our laboratory, we fabricate the WS films ( $WTe_2$ ,  $MoTe_2$ , and  $Co_2MnGa$ ) using magnetron sputtering system with in-situ annealing process. The magnetron sputtering technique is beneficial for massive production with low cost and easy controllability, which is compatible with current industrial processes. In our research, the  $WTe_2$  ( $MoTe_2$ ) and  $Co_2MnGa$  films are sputtered from a W(Mo)-Te target and a Co-Mn-Ga target respectively in an ultrahigh vacuum sputter system. The in-situ annealing temperature during the deposition ranges from room temperature to 600 °C. The surface morphology of the films is characterized by atomic force microscope (AFM). The uniformity and crystalline quality of the films is examined by reflection high energy electron diffraction (RHEED) and x-ray diffraction. Furthermore, the samples are patterned into Hall bars and the transport properties are measured using physical properties measurement system (PPMS).

### 4. 研究成果

(1) A sizeable spin Hall effect in sputtered  $WTe_2$  Weyl semimetal based spintronic structures.

The films of  $WTe_2$  and  $MoTe_2$ , were fabricated by sputtering. The structural properties were characterized by x-ray diffraction (XRD), as shown in Figure 1. In addition to the peaks from the substrates, there is no clear peak observed in the XRD patterns, which indicates the 30-nm-thick films have an amorphous-like structure. A ferromagnetic layer of  $CoFeB$  with  $AlO_x$  capping layer was deposited on the  $WTe_2$  with varying thickness from 2 to 8 nm. Furthermore, Hall bar structures were microfabricated for the measurement of spin Hall magnetoresistance (SMR). The illustration of SMR measurement and Hall bar image are shown in Figure 2(a) and 2(b). A SMR ratio of  $\sim 0.05\%$  was observed in the sample of  $WTe_2(2\text{ nm})/CoFeB(2.5\text{ nm})/AlO_x$  at room temperature, as shown in Figure 2(c), which is comparable to that in the Pt/YIG system. By fitting the thickness dependence of the SMR, the spin Hall angle of  $WTe_2$  was estimated to be  $\sim -0.04$  with a spin diffusion length of 2.5 nm at room temperature. The experimental demonstration of the spin orbit effect in sputtered WSs could contribute the progress of the development of WS-based spintronic devices.

(2) Discovery of the degree of order dependence of AHE in  $Co_2MnGa$  Weyl semimetal thin

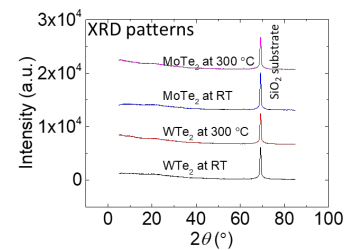


Figure 1, XRD patterns for the  $WTe_2(30\text{ nm})$  and  $MoTe_2(30\text{ nm})$  deposited at room temperature and 300 °C, respectively.

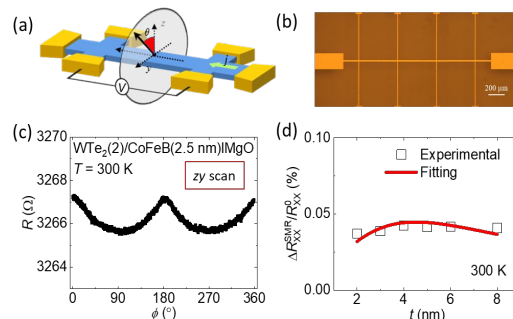


Figure 2, SMR in the  $WTe_2/CoFeB/AlO_x$  heterostructures. (a,b) illustration and image of Hall bar. (c) SMR raw data. (d)  $WTe_2$  thickness dependence of SMR.

films.

The  $\text{Co}_2\text{MnGa}$  films with the thickness of 30 nm were deposited by the sputter system at different deposition temperatures of RT, 200 °C, 400 °C, 500 °C and 600 °C, respectively.

The structures of the thin films were characterized by XRD with out-of-plane and in-plane scans. Figure 3(a) shows the out-of-plane XRD patterns for the series of samples. The (002) and (004) peaks were observed for all the samples deposited regardless of the deposition temperature, which indicates the films were grown along (001) orientation on the MgO(001) substrates. The intensity of the peaks increases with the

increase of deposition temperature, which could be due to the increased degree of order at high deposition temperatures. Figures 3(b) shows the XRD patterns for the 111 peaks, which were detected by tilting the samples to  $\chi = 54.7^\circ$ . For the thin films deposited at RT and 200 °C, no (111) peaks were observed. With increasing the deposition temperature, the (111) peak appeared and was clearly observed at the temperatures of 500 °C and 600 °C. The intensity of the peak increased with the deposition temperature, indicating the increased degree of order at high deposition temperatures. The degree of order of the samples were plotted as a function of deposition temperature, as shown in Fig. 3(c). The  $\text{Co}_2\text{MnGa}$  films possess two kinds of ordering structures:  $L2_1$  and  $B2$  structures. The degree of order for  $B2$  structure increases with increasing the deposition temperature from RT to 400 °C, then is nearly saturated with a degree of  $B2$ -ordering of ~80% from 400 °C to 600 °C. The degree of order for  $L2_1$  structure starts to increase at 400 °C. The maximum degree of  $L2_1$ -ordering of 40% was achieved in the sample deposited at 600 °C.

Figure 4(b) shows the dependence of longitudinal resistivity on the measurement temperature. For the samples deposited RT, the longitudinal resistivity is nearly independent of measurement temperature. It is found that the difference of the longitudinal resistivities between 10 K and 300 K increases with increasing the deposition temperature. For the sample deposited at 600 °C, the longitudinal resistivity decreases with the decrease of measurement temperature. Figure 4 (c) shows the dependence of anomalous Hall resistivity on the measurement temperature. The transverse resistivity increases with decreasing the measurement temperature. Figure 5 indicates the dependence of anomalous Hall angle on the measurement temperature. Large anomalous Hall angles were achieved for the samples deposited at 400 °C, 500 °C, and 600 °C. Considering the ordering structure, it is found that the samples containing  $L2_1$  order show enhanced AHE compared to  $B2$ -ordered samples, which could be attributed to the electronic band structures. By further investigating the dependence of Hall conductivity on longitudinal conductivity, we found

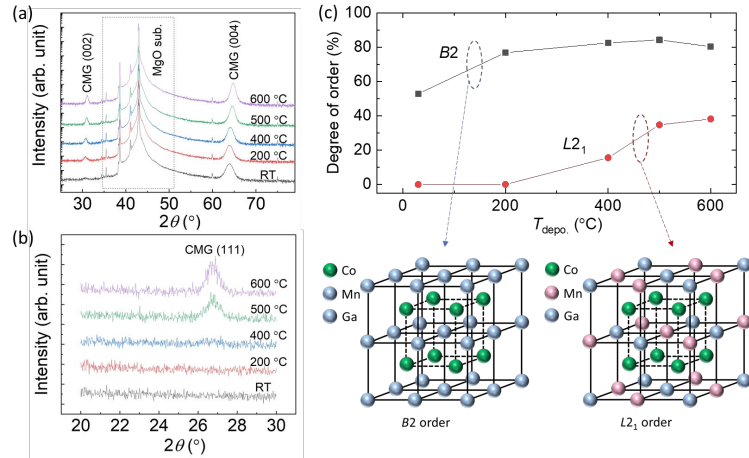


Figure 3. The degree of order of  $\text{Co}_2\text{MnGa}$  as a function of annealing temperature. (a) XRD out-of-plane scan. (b) XRD patterns for CMG111 peaks. (c)  $T_{\text{depo}}$  dependence of the ordering degree of CMG.

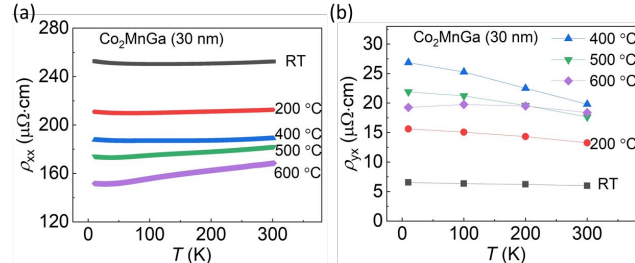


Figure 4. The temperature dependence of (a) longitudinal resistivity and (b) anomalous Hall resistivity for 30-nm-thick  $\text{Co}_2\text{MnGa}$  deposited at different temperatures.

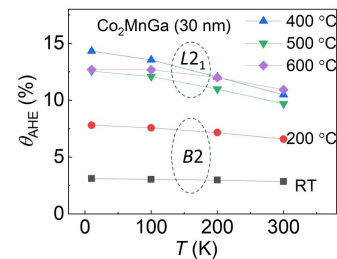


Figure 5. Anomalous Hall angle as a function of temperature with  $L2_1$  and  $B2$  ordered phases.

様 式 C - 19、F - 19 - 1、Z - 19、CK - 19 (共通)

that the dominant contribution to AHE is the intrinsic contribution. This research can contribute to the design of Ws-based materials with large spin-orbit effects by structural order control.

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